Ricardo Ruiz

List of Publications by Year in descending order

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56 5,821 30 49
papers citations h-index g-index

56 56 56 5881 all docs docs citations times ranked citing authors

#	Article	IF	CITATIONS
1	Density Multiplication and Improved Lithography by Directed Block Copolymer Assembly. Science, 2008, 321, 936-939.	12.6	1,099
2	Pentacene Thin Film Growth. Chemistry of Materials, 2004, 16, 4497-4508.	6.7	588
3	Magnetic recording at 1.5ÂPbÂmâ^2 using an integrated plasmonic antenna. Nature Photonics, 2010, 4, 484-488.	31.4	412
4	Polymer self assembly in semiconductor microelectronics. IBM Journal of Research and Development, 2007, 51, 605-633.	3.1	397
5	Thickness Dependence of Mobility in Pentacene Thin-Film Transistors. Advanced Materials, 2005, 17, 1795-1798.	21.0	309
6	Nanoscale chemical imaging by photoinduced force microscopy. Science Advances, 2016, 2, e1501571.	10.3	228
7	Pentacene ultrathin film formation on reduced and oxidized Si surfaces. Physical Review B, 2003, 67, .	3.2	204
8	Directed Assembly of Lamellae- Forming Block Copolymers by Using Chemically and Topographically Patterned Substrates. Advanced Materials, 2007, 19, 607-611.	21.0	196
9	Bit-Patterned Magnetic Recording: Theory, Media Fabrication, and Recording Performance. IEEE Transactions on Magnetics, 2015, 51, 1-42.	2.1	179
10	Dynamic Scaling, Island Size Distribution, and Morphology in the Aggregation Regime of Submonolayer Pentacene Films. Physical Review Letters, 2003, 91, 136102.	7.8	172
11	Structure of pentacene thin films. Applied Physics Letters, 2004, 85, 4926-4928.	3.3	163
12	Control of Self-Assembly of Lithographically Patternable Block Copolymer Films. ACS Nano, 2008, 2, 1396-1402.	14.6	149
13	The Limits of Lamellae-Forming PS- <i>b</i> -PMMA Block Copolymers for Lithography. ACS Nano, 2015, 9, 7506-7514.	14.6	128
14	Induced Orientational Order in Symmetric Diblock Copolymer Thin Films. Advanced Materials, 2007, 19, 587-591.	21.0	124
15	Self-Assembly Based Plasmonic Arrays Tuned by Atomic Layer Deposition for Extreme Visible Light Absorption. Nano Letters, 2013, 13, 3352-3357.	9.1	118
16	Rectangular Patterns Using Block Copolymer Directed Assembly for High Bit Aspect Ratio Patterned Media. ACS Nano, 2011, 5, 79-84.	14.6	107
17	High-Resolution PFPE-based Molding Techniques for Nanofabrication of High-Pattern Density, Sub-20 nm Features: A Fundamental Materials Approach. Nano Letters, 2010, 10, 1421-1428.	9.1	96
18	Local Defectivity Control of 2D Selfâ€Assembled Block Copolymer Patterns. Advanced Materials, 2007, 19, 2157-2162.	21.0	92

#	Article	IF	Citations
19	Directed Self-Assembly of POSS Containing Block Copolymer on Lithographically Defined Chemical Template with Morphology Control by Solvent Vapor. Macromolecules, 2012, 45, 292-304.	4.8	91
20	Early stages of pentacene film growth on silicon oxide. Organic Electronics, 2004, 5, 257-263.	2.6	84
21	Bit Patterned Media at 1 Tdot/in ² and Beyond. IEEE Transactions on Magnetics, 2013, 49, 773-778.	2.1	75
22	Evolutionary Optimization of Directed Self-Assembly of Triblock Copolymers on Chemically Patterned Substrates. ACS Macro Letters, 2014, 3, 747-752.	4.8	64
23	Directed Self-Assembly of Triblock Copolymer on Chemical Patterns for Sub-10-nm Nanofabrication <i>via</i> Solvent Annealing. ACS Nano, 2016, 10, 7855-7865.	14.6	62
24	Strong Coupling of Plasmon and Nanocavity Modes for Dual-Band, Near-Perfect Absorbers and Ultrathin Photovoltaics. ACS Photonics, 2016, 3, 456-463.	6.6	61
25	Double-Patterned Sidewall Directed Self-Assembly and Pattern Transfer of Sub-10 nm PTMSS- <i>b</i> -PMOST. ACS Applied Materials & Interfaces, 2015, 7, 13476-13483.	8.0	60
26	Growth dynamics of pentacene thin films: Real-time synchrotron x-ray scattering study. Physical Review B, 2006, 73, .	3.2	56
27	Image quality and pattern transfer in directed self assembly with block-selective atomic layer deposition. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2012, 30, .	1.2	52
28	Topcoat Approaches for Directed Self-Assembly of Strongly Segregating Block Copolymer Thin Films. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 55-58.	0.3	52
29	Nine-fold density multiplication of hcp lattice pattern by directed self-assembly of block copolymer. Polymer, 2009, 50, 4250-4256.	3.8	45
30	Heat-assisted magnetic recording media materials. MRS Bulletin, 2018, 43, 93-99.	3.5	32
31	Fabrication of templates with rectangular bits on circular tracks by combining block copolymer directed self-assembly and nanoimprint lithography. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2012, 11, 031405-1.	0.9	30
32	Template–polymer commensurability and directed selfâ€assembly block copolymer lithography. Journal of Polymer Science, Part B: Polymer Physics, 2015, 53, 595-603.	2.1	26
33	Ordering poly(trimethylsilyl styreneâ€∢i>blockâ€∢scp> <i>D</i> , <i>L</i> â€lactide) block copolymers in thin films by solvent annealing using a mixture of domainâ€selective solvents. Journal of Polymer Science, Part B: Polymer Physics, 2014, 52, 36-45.	2.1	25
34	Rapid directed self assembly of lamellar microdomains from a block copolymer containing hybrid. Applied Physics Letters, 2007, 91, 143106.	3.3	24
35	20nm Pitch Directed Block Copolymer Assembly Using Solvent Annealing for Bit Patterned Media. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 145-148.	0.3	22
36	Bit-Patterned Magnetic Recording: Nanoscale Magnetic Islands for Data Storage., 2009, , 237-274.		22

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37	Self-Registered Self-Assembly of Block Copolymers. ACS Nano, 2017, 11, 7666-7673.	14.6	20
38	Transfer of self-aligned spacer patterns for single-digit nanofabrication. Nanotechnology, 2015, 26, 085304.	2.6	19
39	Directed self-assembly of high-chi block copolymer for nano fabrication of bit patterned media via solvent annealing. Nanotechnology, 2016, 27, 415601.	2.6	19
40	Line Roughness in Lamellae-Forming Block Copolymer Films. Macromolecules, 2017, 50, 1037-1046.	4.8	17
41	Fabrication of chevron patterns for patterned media with block copolymer directed assembly. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2011, 29, 06F204.	1.2	14
42	Self-Assembly and Directed Assembly of Polymer Grafted Nanocrystals via Solvent Annealing. Macromolecules, 2017, 50, 9636-9646.	4.8	14
43	Practical implementation of order parameter calculation for directed assembly of block copolymer thin films. Journal of Polymer Science, Part B: Polymer Physics, 2010, 48, 2589-2603.	2.1	13
44	Impact of Out-of-Plane Translational Order in Block Copolymer Lithography. Macromolecules, 2011, 44, 9196-9204.	4.8	12
45	Bit patterned media optimization at $1\mathrm{Tdot/in2}$ by post-annealing. Journal of Applied Physics, 2014, $116,.$	2.5	12
46	Integration of Servo and High Bit Aspect Ratio Data Patterns on Nanoimprint Templates for Patterned Media. IEEE Transactions on Magnetics, 2012, 48, 2757-2760.	2.1	11
47	Self-assembly for electronics. MRS Bulletin, 2020, 45, 807-814.	3.5	10
48	Control of Morphology Orientation in Lithographically Patternable Diblock Copolymers. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2007, 20, 519-522.	0.3	4
49	Fabrication of templates with rectangular bits on circular tracks by combining block copolymer directed self-assembly and nanoimprint lithography. , 2012, , .		4
50	Path to Move Beyond the Resolution Limit with Directed Self-Assembly. ACS Applied Materials & Amp; Interfaces, 2019, 11, 20333-20340.	8.0	4
51	Pulsed laser deposition of conductive metallo-dielectric optical filters. Applied Physics A: Materials Science and Processing, 2002, 74, 307-310.	2.3	3
52	<title>Injection of light into a planar dielectric waveguide of metallic walls</title> ., 2001,,.		1
53	Growth and Morphology of Pentacene Films on Oxide Surfaces. Materials Research Society Symposia Proceedings, 2001, 708, 10541.	0.1	0
54	Special Section Guest Editorial: Alternative Lithographic Technologies. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2014, 13, 031301.	0.9	0

#	Article	IF	CITATIONS
55	Special Section Guest Editorial: Alternative Lithographic Technologies IV. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2015, 14, 031201.	0.9	О
56	Special Section Guest Editorial: Alternative Lithographic Technologies V. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2016, 15, 031601.	0.9	0